# **Polymerization-Induced Phase Separation near Patterned Surface**



Alexey A. Gavrilov, Elena N.Govorun, <u>Alexander V. Chertovich</u>

Physics Department, Moscow State University, Leninskie Gory, Moscow 119991, Russia E-mail: chertov@polly.phys.msu.ru



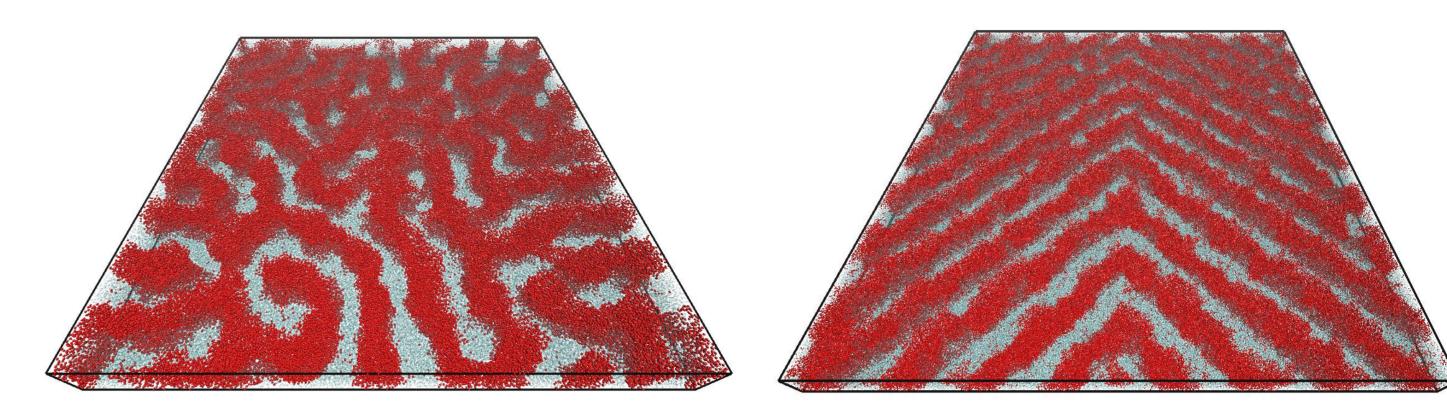
### Systems and methods

•Polymerization-induced microphase separation (PIPS) in thin films •Initially homogeneous blend of two types (A and B) of monomers at  $0 < \chi < 2$ 

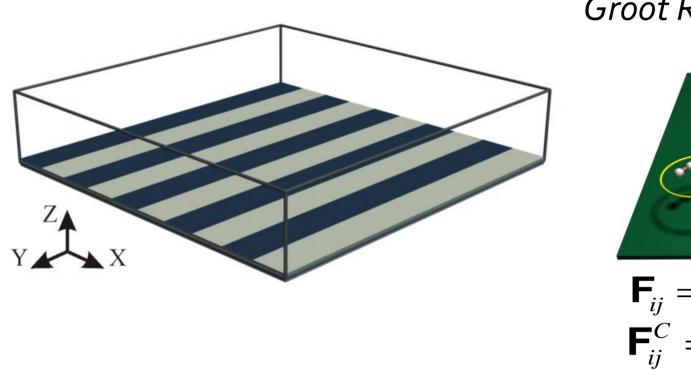
Long blocks formed during copolymerisation segregate from each other

•The reaction probabilities  $p_{AA} = p_{BB}$  and  $p_{AB} = p_{BA}$  are the model parameters

### RESULTS



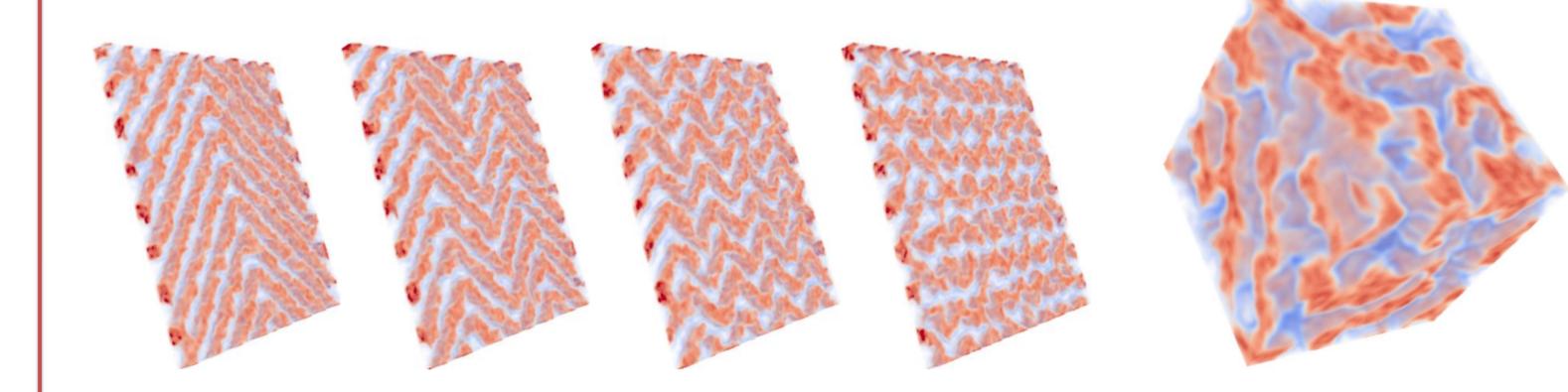
### Method of simulations: dissipative particle dynamics



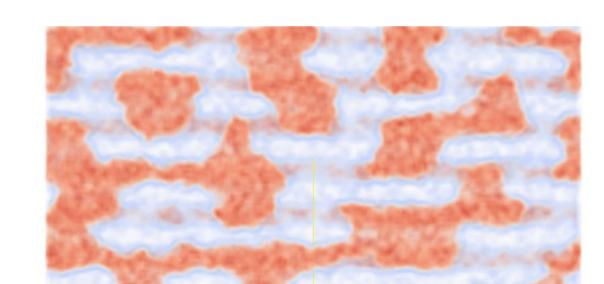
Chemically Heterogeneous Surface

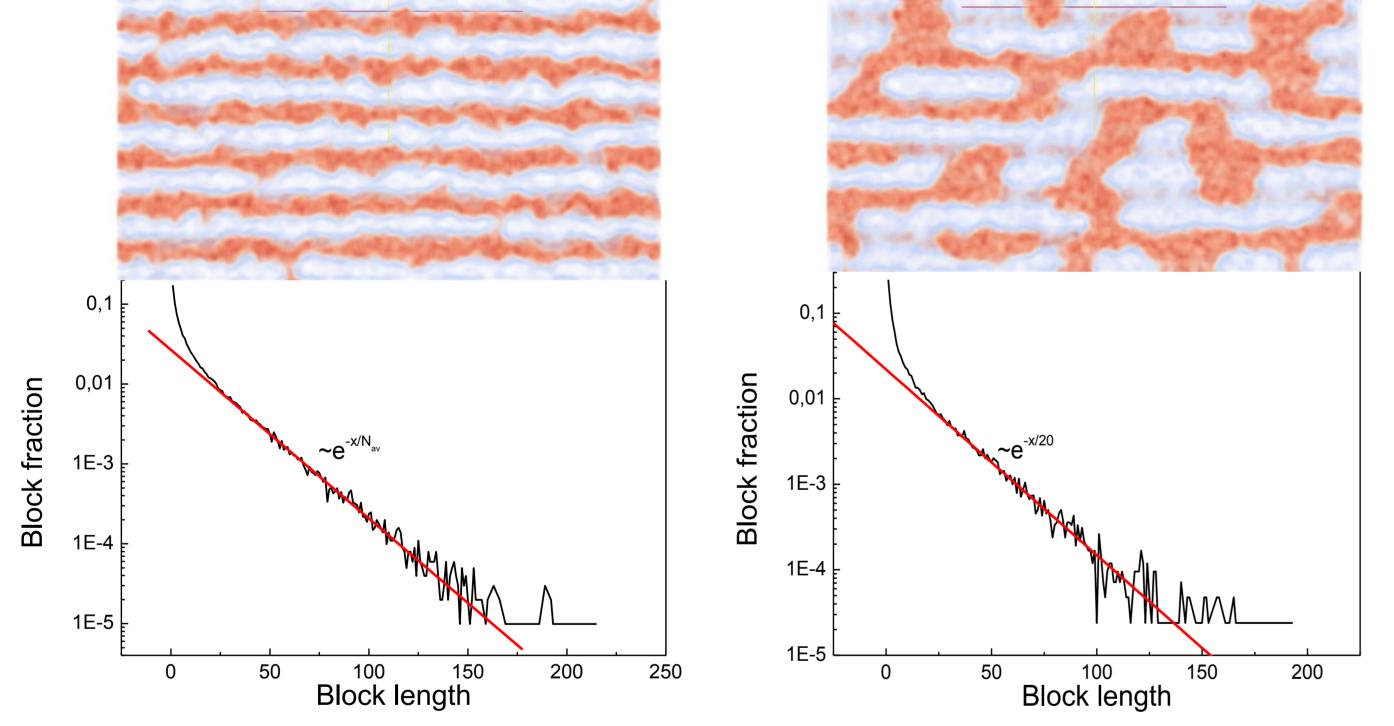
Groot R.D. and Warren P.B. J. Chem. Phys. **107** (1997) 4423  $F_{ij}^{D} = -\gamma \omega^{2} (r_{ij})(\mathbf{r}_{ij} \cdot \mathbf{V}_{ij})\mathbf{r}_{ij}$   $F_{ij}^{D} = -\gamma \omega^{2} (r_{ij})(\mathbf{r}_{ij} \cdot \mathbf{V}_{ij})\mathbf{r}_{ij}$   $F_{ij}^{D} = -\gamma \omega^{2} (r_{ij})(\mathbf{r}_{ij} \cdot \mathbf{V}_{ij})\mathbf{r}_{ij}$   $F_{ij}^{R} = \sqrt{2k_{B}T\gamma}\xi_{ij}\omega(r_{ij})\mathbf{r}_{ij}$   $F_{ij}^{R} = \sqrt{2k_{B}T\gamma}\xi_{ij}\omega(r_{ij})\mathbf{r}_{ij}$   $G(r_{ij}) = \begin{cases} 1 - r_{ij} / r_{cut} & r_{ij} \leq r_{cut} \\ 0 & r_{ij} > r_{cut} \\ 0 & r_{ij} > r_{cut} \end{cases}$   $F_{ij}^{R} = \sqrt{2k_{B}T\gamma}\xi_{ij}\omega(r_{ij})\mathbf{r}_{ij}$   $F_{ij}^{random}$ 

•The pattern facilitates the formation of structures with long-range order, which are stable after the removal of the pattern



### **Reaction Parameters**

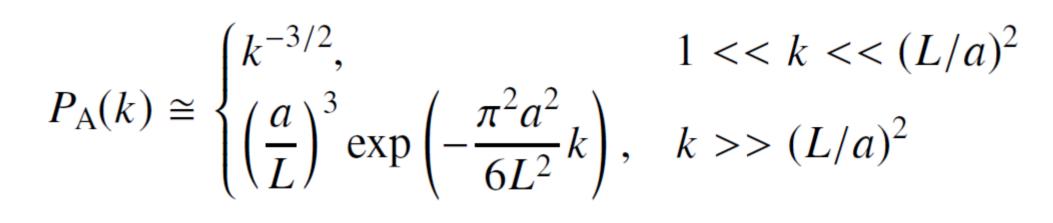


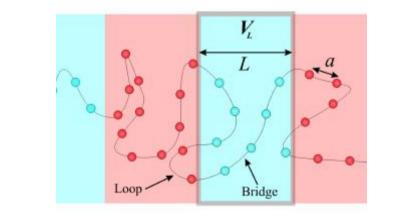


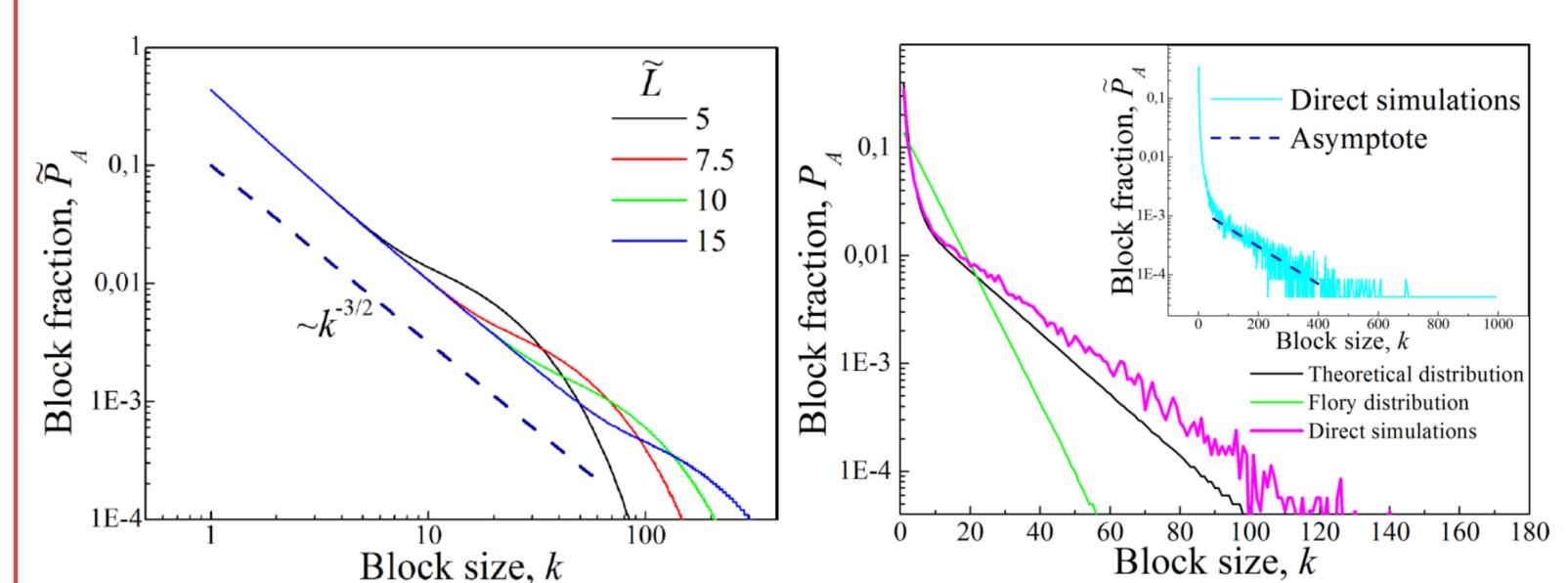
If the reaction probabilities are too low, the resulting structures are very different even though the block-length distributions are the same
In the course of reaction too large aggregates are formed, which probably leads to different distributions of blocks along the polymer chains – the long blocks are segregated from the short ones

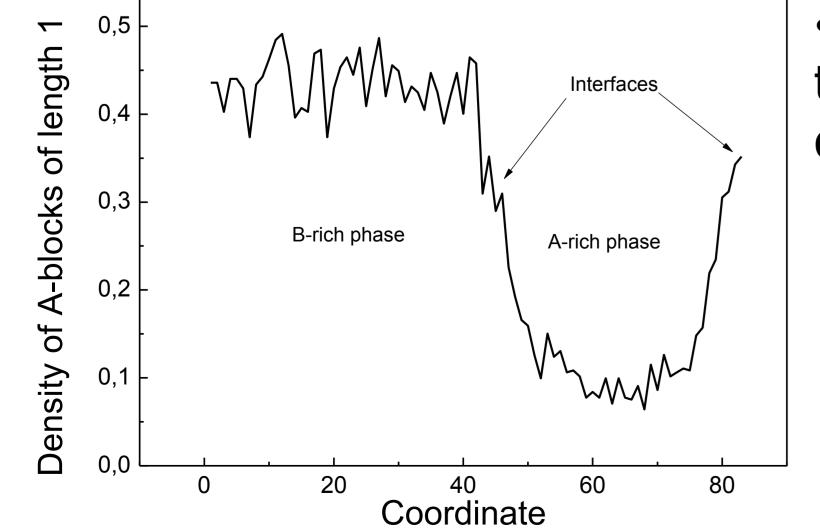
More complex patterns like bends can be reproduced
Bulk copolymerization gives no long-range structure

## Some theory









•Short blocks are located in the opposite domains, which decreases the roughness

# Conclusions

- The presence of a pattern facilitates the formation of long-range order in melts of copolymers obtained during PIPS.
- Complex patterns can be reproduced
   Similar block-length distributions obtained under different reaction conditions can lead to very different structures due to different block sequences

The authors appreciate the financial support from the Russian Scientific Foundation (project 14-13-00683). We thank Moscow State University Supercomputer Center for providing the computational resources